組立後の洗浄工程削減へ!

Eliminate cleaning process after assembly!

フラックス残渣レスペースト

Less flux residue paste

NP303-FLV-T4

フラックス残渣が残らず洗浄不要!

Since flux residue does not remain, cleaning is unnecessary!

Niなどのヌレにくい母材に対してもヌレ性良好!

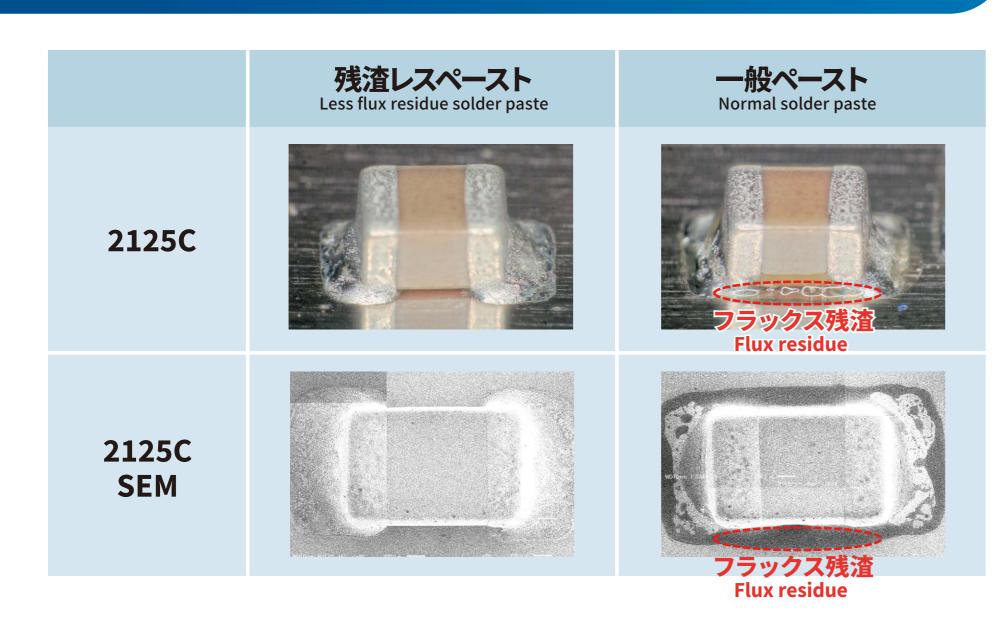
Wettability to the parts that are hard to be wet like Ni are also good!

N2+真空リフロー対応でボイド発生を抑制!

Suppress occurrence of void by N2 + vacuum reflow furnace!

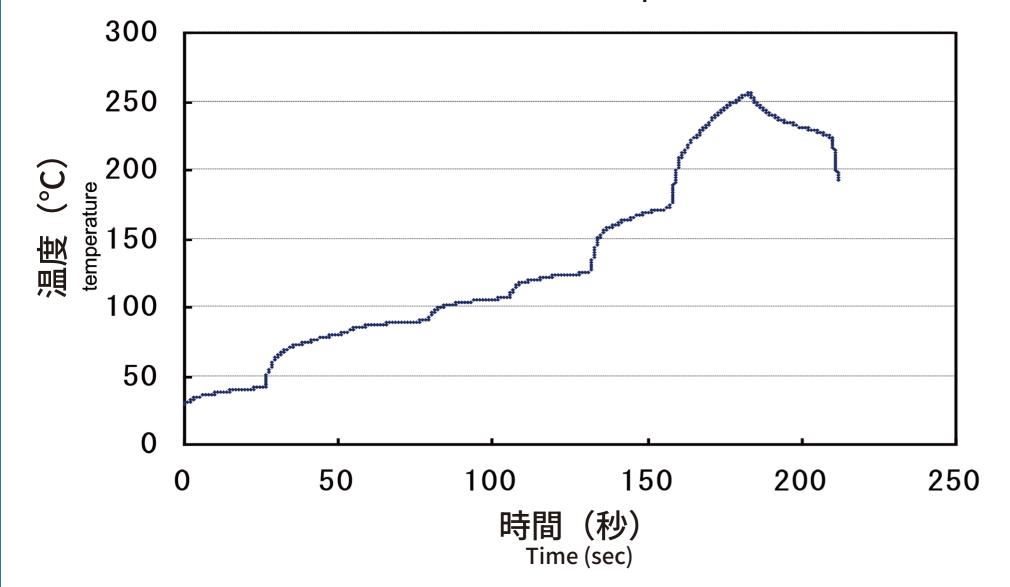
揮発によるフラックス残渣抑制

Suppression of flux residue by volatilization



推奨リフロープロファイル

Recommended reflow profile



| | 試験条件 Test condition | 推奨条件 Recommended conditions |
|--|------------------------|-----------------------------------|
| 昇温速度 Temperature increase rate | 1.0sec. | 2sec.以下 |
| プリヒート(100°C-170°C) Preheat | 60.8sec. | 40-70sec. |
| 昇温速度(170°C-220°C) Temperature increase rate | 4.6°C/sec. | 4°C/sec.以上 |
| >220°C | 46sec. | 30-90sec. |
| ピーク温度 Peak temperature | 260.6°C | 250-270°C |
| 酸素濃度 Oxygen concentration | 500ppm | 500ppm以下 |
| 真 空到達度 Degree of vacuum | 3.9kPa | 10kPa以下 |

ギ酸リフロー対応 フラックス残渣レスペースト

Less flux residue paste applied for formic acid reflow

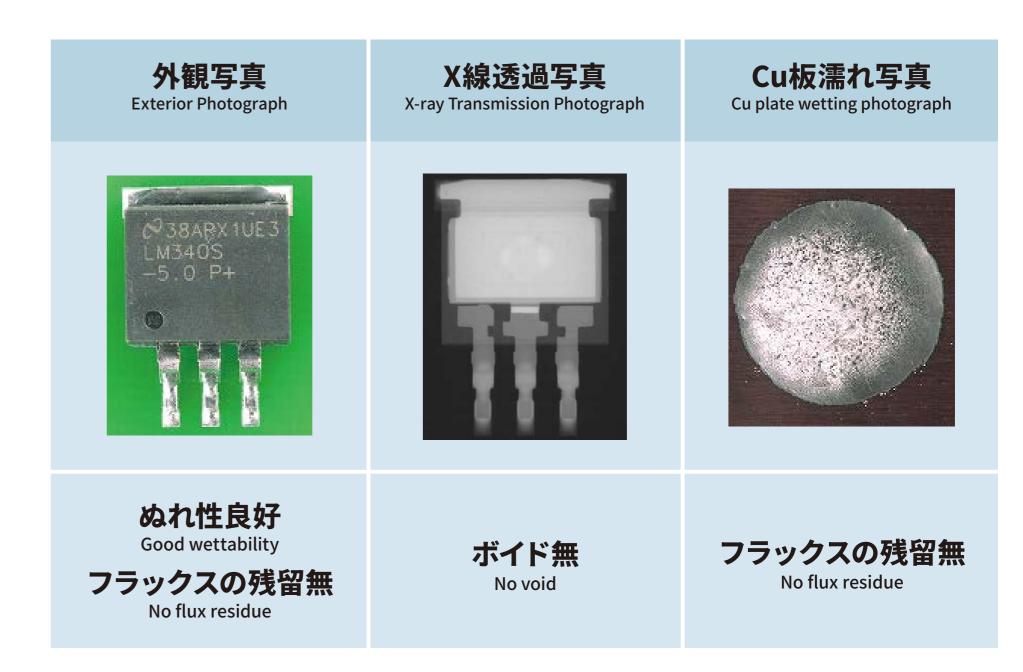
NP303-FL001-T4

ギ酸リフローによりフラックス残渣、ボイドゼロ!

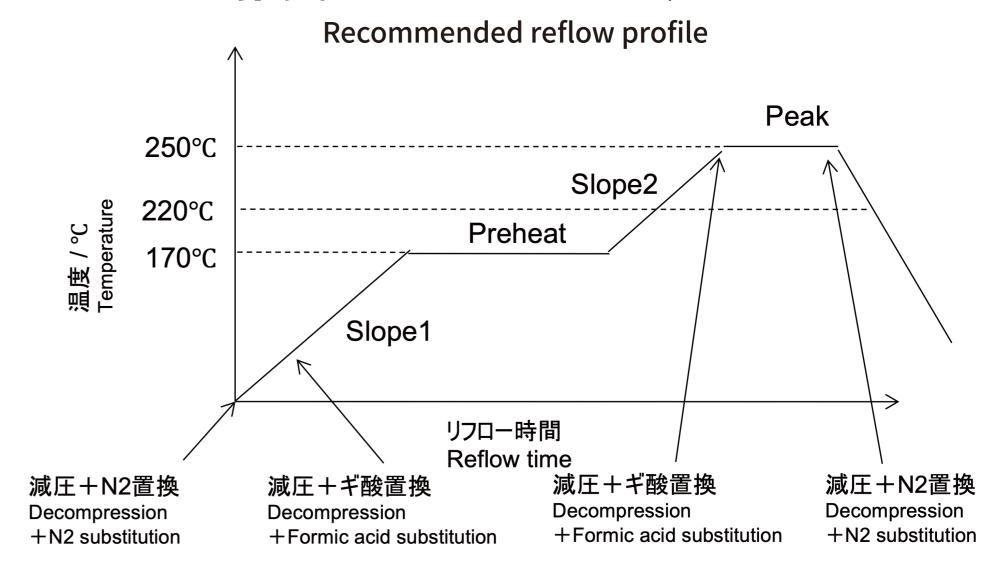
No flux residue and void due to formic acid reflow!

ギ酸リフロー性の検証結果

Test result of reflowability for Formic acid reflow



推奨リフロープロファイル



| Step | 条件 Conditions | |
|--|---|--|
| Slope1, 2 | 2.0°C/sec以内 within 2.0°C/sec | |
| Preheat | 170°C、60sec以上 more than 170°C60sec | |
| Peak | Sn3Ag0.5Cuの融点 (217°C)+15°C以上 melting point of Sn3Ag0.5Cu+more than 15°C | |
| 220°C以上 (半田の融 点以上) More than 220°C(more than melting point of solder) | 30sec以上 more than 30sec | |
| ギ酸導入のタイミング Supply timing of formic acid | Preheat前とPeak温度前に2回 Total of 2 times before preheat and peak temperature | |

